



Software solutions for  
optimizing micro & nano  
fabrication processes



## Third Announcement

# BEAMeeting MNE-Berlin 2023 Technical Workshop & Discussion



**Time:** Monday, September 25<sup>th</sup>, 2023 9:00 – 12:30 CEST  
12:30 – 16:00 (India) / 15:00 – 18:30 (China) / 16:00 – 19:30 (Japan)  
**Location:** [Mercure Hotel MOA Berlin](#), Stephanstraße 41, 10559 Berlin, Germany  
Online via TEAMS (access data will be sent after registration shortly before the BEAMeeting)

BEAMeetings are a technical exchange platform for the direct write community focused on e-Beam and laser lithography, data-preparation, PEC, process correction, and lithography simulation. It is a platform for BEAMER users and those who are interested in GenISys software. We will do our best to arrange a program with interesting presentations. Please see our final agenda. Please do not hesitate to communicate requests and suggestions to make the BEAMeeting most interesting and valuable for the BEAMER community.

Please save the date in your calendar and register our BEAMeeting:

For REGISTRATION, please click here:

[REGISTER On-Site](#)  
[REGISTER Online](#)

or visit our Homepage for the details: [BEAMeeting MNE-Berlin 2023](#)

To support the next generation of lithographers and nanofabricators, GenISys organized interesting talks with students (BA, MSc, PhD) and awarded prizes, which made our BEAMeeting even more exciting.

The BEAMeeting is free of charge. Please feel free to share this information with interested colleagues who may wish to join the BEAMeeting.

Please do not hesitate to contact us ([marketing@genisys-gmbh.com](mailto:marketing@genisys-gmbh.com)) if you have any questions or any suggestions.

We are looking forward to presenting you with an interesting and valuable workshop!

Thank you,  
The GenISys Team

# BEAMeeting MNE-Berlin 2023

## Technical Workshop & Discussion

Date: Monday, Sept. 25th, 2023 - Time: 09:00 – 12:30 pm

Berlin – Germany & Online

### Final Agenda

Mike Butler GenISys	Welcome & Introduction	9:00
Nezih Ünal GenISys	GenISys Update	9:10
Hendrik Boerma Fraunhofer Heinrich Hertz Institute (HHI)	Simulation, dataprep, Prozessierung und Analyse von optischen Wellenleiterstrukturen basierend auf Inverse Design	9:30
Marcus Rommel Chalmers University of Technology	Optimization of Josephson junctions with the help of Chipscanner and the Beamer bias module.	9:50
Zach Degnan The University of Queensland	Optimising EBL fabrication for low loss photonics	10:10
	Coffee Break	10:30
Analia Fernandez Herrero Helmholtz-Zentrum Berlin	Variable space gratings produced by grey scale e- beam lithography for boosting grating efficiency	10:50
Alexander Fernandez-Scarioni Physikalisch Technische Bundesanstalt	Quantum devices at the PTB	11:10
Sven Bauerdick GenISys	ProSEM: What's New and Feedback	11.30
Thomas Michels GenISys	Update in BEAMER /TRACER /LAB Roadmap, Wishes & Discussion	11.50
	Break	12:30
Afternoon:	Maskless Laser Lithography for Advanced Micro- and Nanofabrication	13:30
	Closing	17:30